













**Figure 5.** [(a) and (b)] STEM HAADF images of the surface of a layer grown on a substrate with  $[00\bar{1}]$  and  $[001]$  step-down directions, respectively. The magnified regions show the typical step morphology in the  $[010]$  projection. (c) shows a stick and ball model of the observed step structure. Bright and dark green balls correspond to tetrahedrally and octahedrally bound Ga columns, respectively. Red, orange, and yellow balls correspond to the 3 different oxygen positions O(I), O(II), and O(III), respectively.

## Conclusions and implications

Our experimental and theoretical work has shown that the differences in surface energies in  $\beta$ - $\text{Ga}_2\text{O}_3$  have strong implications on homoepitaxial growth. Faceting originates from surface energy minimization and appears to be reciprocal in case of etching and growth. In fact, a detailed study on surface energy as dependent on the chemical potential still has to be performed by both experiment and theory. Up to now, the  $(100)$  surfaces is the only one that shows the desired step flow growth. However, we have also shown that formation of low energy facets at steps and the low symmetry of the monoclinic lattice has strong implications when choosing the right miscut in  $\beta$ - $\text{Ga}_2\text{O}_3$ . Unexpectedly the  $(\bar{2}01)$  surface has a surface energy that is even lower than that of the second cleavage plane  $(001)$ . In spite of the fact that substrates with large diameter with these orientations are available it might be worth to study growth on this surface. As in the case of the  $(100)$  surface choosing the appropriate miscut might be the key to get high quality layers.

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